

Dielectric Solids Division Fachverband Dielektrische Festkörper (DF)

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Overview of Invited Talks and Sessions

(lecture rooms ER 164, EB 107 and EB 407; Poster G)

Invited Talks

DF 2.1	Mon	10:00–10:40	EB 107	Recent Progress in Polymeric LED — ●KLAUS MEERHOLZ
DF 4.1	Mon	14:00–14:40	EB 107	High-k gate dielectrics on silicon and on high-mobility semiconductors: Atomic-scale phenomena underlying transistor performance — ●MARTIN M. FRANK
DF 5.1	Mon	14:30–15:10	EB 407	Behaviour of Ferroelectrics Influenced by Nanoscale Morphology — ●JOHN MARTIN GREGG, ALINA SCHILLING, LIWU CHANG, MARK MCMILLEN, MOHAMED SAAD, ROBERT BOWMAN, GUSTAU CATALAN, JAMES SCOTT, FINLAY MORRISON
DF 6.1	Tue	9:30–10:00	EB 407	Glass freezing in confined geometries studied by DMA — ●WILFRIED SCHRANZ, JOHANNES KOPPENSTEINER, MADALINA-ROXANA PUICA
DF 7.1	Tue	10:00–10:40	EB 107	Modelling of Point Defects in Ferroelectric Materials — ●KARSTEN ALBE, PAUL ERHART
DF 7.2	Tue	10:40–11:20	EB 107	Polarons in lithium niobate — ●ORTWIN SCHIRMER
DF 12.1	Thu	10:00–10:40	EB 107	Piezoelectric ceramic materials - a success story — ●DIETER SPORN, ANDREAS SCHÖNECKER, BERNHARD BRUNNER, HORST BEIGE

Tutorial "Basics of polar oxides"

DF 1.1	Sun	14:00–15:30	ER 164	Physik der Ferroelektrika - Grundlagen — ●CHRISTOPH BUCHAL
DF 1.2	Sun	15:30–17:00	ER 164	Ferroelektrische Schichten und Heterostrukturen — ●HERMANN KOHLST-EDT

Internal symposium "High-k dielectrics for highly scaled Silicon-based Micro- and Nanoelectronics"

Organisation: Th. Schroeder, IHP-Microelectronics, Frankfurt/Oder

DF 4.1	Mon	14:00–14:40	EB 107	High-k gate dielectrics on silicon and on high-mobility semiconductors: Atomic-scale phenomena underlying transistor performance — ●MARTIN M. FRANK
DF 4.2	Mon	14:40–15:05	EB 107	Molecular Beam Epitaxy of crystalline oxides on Si for C-MOS and for the monolithic integration of semiconductors on Silicon — ●SAINT-GIRONS GUILLAUME, MERCKLING CLÉMENT, EL-KAZZI MARIO, BECERRA LOIC, REGRENY PHILIPPE, PATRIARCHE GILLES, LARGEAU LUDOVIC, FAVRE-NICOLIN VINCENT, HOLLINGER GUY
DF 4.3	Mon	15:05–15:30	EB 107	Damascene metal gate technology: A solution to high-k gate stack challenges? — ●UDO SCHWALKE
DF 4.4	Mon	15:30–16:10	EB 107	Do new materials solve the upcoming challenges of future DRAM memory cells? — ●UWE SCHRÖDER
DF 4.5	Mon	16:10–16:35	EB 107	AVD and ALD developments for next generation MIM capacitors and memory applications — PETER K. BAUMANN, CHRISTOPH LOHE, ●MICHAEL HEUKEN

DF 4.6 Mon 16:35–17:00 EB 107 **MIM Capacitors for Wireless Communication Technologies** —
•CHRISTIAN WENGER

Internal symposium "Point defect spectroscopy and engineering"

Organisation: R. Eichel, Technische Universität Darmstadt

DF 7.1 Tue 10:00–10:40 EB 107 **Modelling of Point Defects in Ferroelectric Materials** — •KARSTEN ALBE, PAUL ERHART

DF 7.2 Tue 10:40–11:20 EB 107 **Polarons in lithium niobate** — •ORTWIN SCHIRMER

DF 7.3 Tue 11:20–11:40 EB 107 **Local structure and symmetry of paramagnetic ions in microscopic and nanoscopic ferroelectric materials** — •EMRE ERDEM, KAMIL KIRAZ, MEHMET SOMER, RÜDIGER -A. EICHEL

DF 7.4 Tue 11:40–12:00 EB 107 **The effect of (Gd³⁺,Cu²⁺) and (Gd³⁺,Fe³⁺) Co-Doping on the Defect Chemistry of PbTiO₃** — •MICHAEL DRAHUS, RÜDIGER EICHEL, EMRE ERDEM, HANS KUNGL, MICHAEL HOFFMAN

DF 7.5 Tue 12:00–12:20 EB 107 **Influence of extrinsic defects on the recombination behavior of light-induced hole and electron polarons in KNbO₃** — •BETTINA SCHOKE, CHRISTOPH MERSCHJANN, STEFAN TORBRÜGGE, MIRCO IMLAU

DF 7.6 Tue 12:20–12:40 EB 107 **Solid-state NMR on defects in lead titanates** — •MARKO BERTMER, RÜDIGER EICHEL, HANS KUNGL

DF 7.7 Tue 12:40–13:00 EB 107 **Gitterplatzbestimmung und Ausheilverhalten von Hf implantiertem CaF₂** — •THOMAS GERUSCHKE, REINER VIANDEN

Invited talks of the joint symposium SYNf

See SYNf for the full program of the Symposium.

Invited talks of the joint symposium SYEC

See SYEC for the full program of the Symposium.

Sessions

DF 1.1–1.2	Sun	14:00–17:00	ER 164	Tutorial: Basics of Polar Oxides
DF 2.1–2.8	Mon	10:00–13:00	EB 107	Electric, electromechanical and optical properties I
DF 3.1–3.5	Mon	10:40–12:20	EB 407	Phase Transitions
DF 4.1–4.6	Mon	14:00–17:00	EB 107	High-k dielectrics for highly scaled Silicon-based Micro- and Nanoelectronics
DF 5.1–5.8	Mon	14:30–17:30	EB 407	Scanning and diffraction methods
DF 6.1–6.10	Tue	9:30–12:15	EB 407	Glasses I (joint session DF/DY)
DF 7.1–7.7	Tue	10:00–13:00	EB 107	Point defect spectroscopy and engineering
DF 8.1–8.7	Tue	14:30–16:15	EB 407	Glasses II (joint session DF/DY)
DF 9.1–9.19	Tue	15:00–18:00	Poster G	Poster
DF 10.1–10.7	Wed	14:30–16:15	EB 407	Glasses III (joint session DF/DY)
DF 11.1–11.9	Wed	14:00–17:00	EB 107	Dielectric and ferroelectric thin films and nanostructures I
DF 12.1–12.8	Thu	10:00–13:00	EB 107	Dielectric and ferroelectric thin films and nanostructures II
DF 13.1–13.9	Thu	14:00–17:00	EB 107	Dielectric and ferroelectric thin films and nanostructures III
DF 14.1–14.10	Thu	14:00–17:20	EB 407	Electric, electromechanical and optical properties II

Annual General Meeting of the Dielectric Solids Division

Mittwoch 17:30–18:30 Raum EB 107

- Bericht des Fachverbandsleiters
- Tagungsnachlese
- Eingeladene Vorträge für 2009
- Fachinterne und fachübergreifende Symposia 2009
- Verschiedenes